



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#9/I.DS.
6/19/03
Nan H

Application Serial No. 09/652,550
Filing Date August 31, 2000
Inventor Keiji Jong et al.
Assignee KMT Semiconductor, LTD
Group Art Unit 2811
Examiner Quang D. Vu
Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 3-10-03

By: D. Brent Kenady

D. Brent Kenady
Reg. No. 40,045



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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2 Application Serial No. Filed Concurrently Herewith
Filing Date Filed Concurrently Herewith
3 Inventor Keiji Jono et al.
Assignee Micron Technology, Inc. and KMT Semiconductor, LTD
4 Group Art Unit Unknown
Examiner Unknown
5 Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
6 Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
7 Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMS

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9 INFORMATION DISCLOSURE STATEMENT
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12 References -- See attached Form PTO-1449
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14 The citations listed, copies attached, may be material to the examination of the
15 subject application and are therefore submitted in compliance with the duty of
disclosure defined in 37 CFR §1.56. The Examiner is requested to make these citations
of official record in this application. No admission is made regarding whether all the
16 submitted references are prior art.

17 The listed references are discussed in the specification under the heading
18 "Background of the Invention".

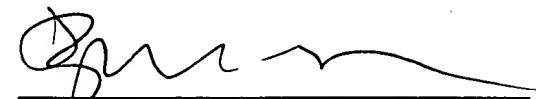
19 The materials cited are presented to assist in and expedite examination of this
20 application. The present invention is considered to be patentable over the cited
21 materials. Expeditious examination and allowance of this application as a patent are
22 therefore urged in order that the public may benefit from the disclosure and
commercialization of the invention.

1
Citation of these references is respectfully requested.

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Respectfully submitted,

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4 Dated: Aug 31, 2000

5 Attorney:

6 
7 Frederick M. Fliegel, Ph.D.
8 Reg. No.: 36,138

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